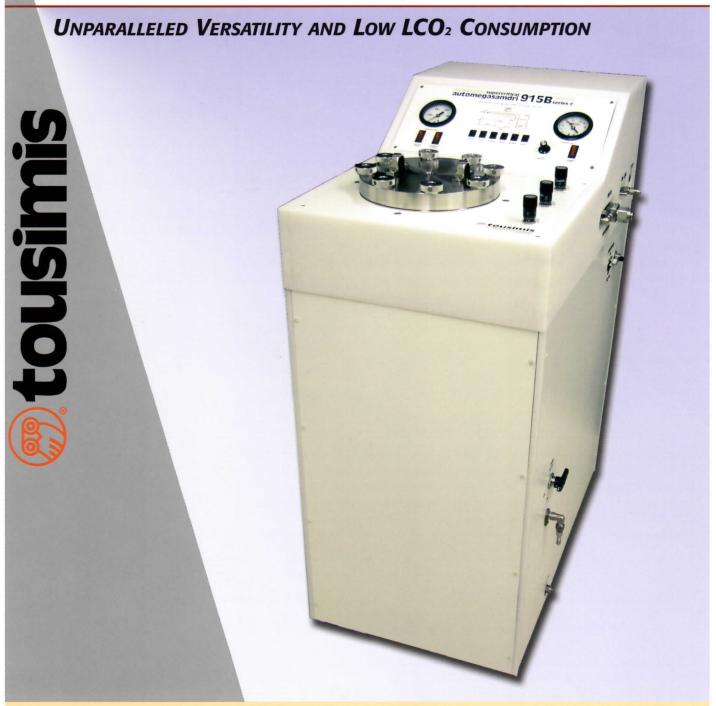
## SUPERCRITICAL CPD MEMS DRYER FOR 6" WAFERS

Automegasamdri®-915B, Series C



- The Automegasamdri\*-915B, Series C maintains tousimis\* process quality and achieves a small facility foot print while utilizing an efficient closed loop refrigeration and waste alcohol collection design.\*
- 35 years of tousimis\* CPD experience enables smooth operation and precise control. HF Compatible Wafer Holders\* and Chamber Inserts\* are provided, allowing flexible CPD processing of various wafer sizes and die.



## SUPERCRITICAL Automegasamdri\*-915B, Series C

Catalog# 8785D (Process Various Wafer Sizes up to 6IN)

- 40% Less LCO2 Consumption.¹
- Process up to 5 wafers in Less than 1 hour.
- All inclusive Small Foot Print design.
- · Minimal installation Site Preparation required.
- On Site Start-Up and User Training included.<sup>2</sup>



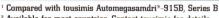
- High efficiency internal closed loop refrigeration.\*
  (22°C to operational in less than 4 minutes)!
- Post-Purge-Filter easily accessible for maintenance ease.\*
- The patented internal SOTER™ condenser\* quietly captures and separates CO<sub>2</sub> exhaust and waste alcohols.
- Unique chamber inserts\* enable variance of chamber I.D. maximizing efficiency in LCO<sub>2</sub> consumption, process time, and providing multiple size wafer process capability!
- Process up to 5 x 6" wafers per process run. Also comes with additional HF Compatible Wafer Holders\* to process 5 x 4", 5 x 3", 5 x 2" diameter wafers or 5 x 10mm square die (tousimis\* HF compatible Wafer Holders\* may be used to etch and process your wafers minimizing handling).
- Chamber illumination with viewing window facilitates chamber status visualization.\*
- · Microprocessor controller allows for completely automatic processing.\*
- All internal surfaces are inert to CO<sub>2</sub> and ultrapure alcohols.
- Repeatable operating parameters insuring "reproducibility" of results.
- Static pressure control module helps insure automatic safe pressure stability.
- Internal filtration system delivers clean LCO2 into process chamber down to 0.4µm.
- · Control panel LED's instantly indicate process mode at a glance.
- · Clean room static-free compatible design.
- All electronic components meet CE, UL and/or U.S. Military Specifications.

## SPECIFICATIONS

- Cabinet: 17.25" (43.8cm) Width x 43" (109.2cm) Height x 29.25" (74.3cm) Depth
- System Set-Up Area Footprint: 24" (61.0cm) Width x 34" (86.4cm) Depth.
- Chamber size: 6.50" I.D. x 1.25" Depth / Chamber volume: 679 ml
- Temperature gauge range: -30°C to 60°C, Pressure gauge range: 0 to 2,000 psi
- 120V / 50-60Hz (Other voltage units also available. Please Inquire)
- LCO<sub>2</sub> flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.\*

## STANDARD ACCESSORIES

- LCO<sub>2</sub> High Pressure braided stainless steel inert Teflon® lined hose. 10ft (~ 3m) long for clean room operation (at a nominal charge, other lengths available upon request ).
- LCO<sub>2</sub> external combination filter assembly (#8784) for water/oil/particulates (down to 0.5μm) pre-installed onto the chamber LCO<sub>2</sub> supply high-pressure hose.
- Tool set included for connecting LCO2 chamber supply line
- · Static free exhaust tubing for all exhaust outlets.
- Internal stainless and nickel scintered filtration systems incorporated to protect lines, wafers, and valves down to 0.4µm.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Complete wafer size process flexibility! 4 chamber inserts\* enable 6.5" chamber ID reduction down to smaller chamber ID sizes for processing wafers and die from a range including: 6", 4", 3", 2", and 1.25"! Allows for multiple wafer size drying.
- 6", 4", 3", 2" diameter wafer holders and 10mm square die holders included. Holders are HF compatible and can hold up to 5 wafers or die each.
- 2 year warranty on all parts and labor. Free lifetime technical support consultations by our scientific staff.



Note: Actual delivered model or accessories may vary slightly, as advancements are constantly being applied.

<sup>2</sup> Available for most countries. Contact tousimis for details.







